1. (original) A maskless lithography system comprising an array of blazed diffractive zone plates, each of which focuses an energy beam into an array of images in order to create a permanent pattern on an adjacent substrate.

2. (original) The maskless lithography system as claimed in claim 1, wherein said blazed diffractive zone plates are blazed Fresnel zone plates.

3. (currently amended) **[~~An~~]** **A** maskless lithography system comprising an array of apodized diffractive elements, each of which focuses an energy beam into an array of images in order to create a permanent pattern on an adjacent substrate at a focal area and is apodized to reduce at least one of the **[~~main or~~]** side lobes in an intensity distribution at a focal area.

4. (original) The maskless lithography system as claimed in claim 3, wherein apodized diffractive elements are Fresnel zone plates.

5. (original) The maskless lithography system as claimed in claim 3, wherein apodized diffractive elements are Fresnel phase plates.

6. (original) The maskless lithography system as claimed in claim 3, wherein apodized diffractive elements are blazed Fresnel zone plates.

7. (original) The maskless lithography system as claimed in claim 3, wherein said apodized diffractive elements are formed of photon sieves.

8. (original) The maskless lithography system as claimed in claim 7, wherein said photon

sieves are amplitude photon sieves.

9. (original) The maskless lithography system as claimed in claim 7, wherein said photon sieves are phase photon sieves.

10. (original) The maskless lithography system as claimed in claim 7, wherein said photonic sieves are alternating phase photonic sieves.

11. (original) A maskless lithography system comprising an array of diffractive elements, each of which focuses an energy beam into an array of images in order to create a permanent pattern on an adjacent substrate and has a focusing efficiency of at least 50%.

12. (original) The maskless lithography system as claimed in claim 11, wherein said diffractive elements are 100% transmissive.

13. (original) The maskless lithography system as claimed in claim 12, wherein said diffractive elements are alternating phase photon sieves.

14. (currently amended) A maskless lithography system comprising an array of **[~~Besel~~]** **Bessel** zone plates, each of which **[~~focuses an energy~~]** **converts an energy** beam into an array of **[~~images~~]** **Bessel beams** in order to create a permanent pattern on an adjacent substrate.